

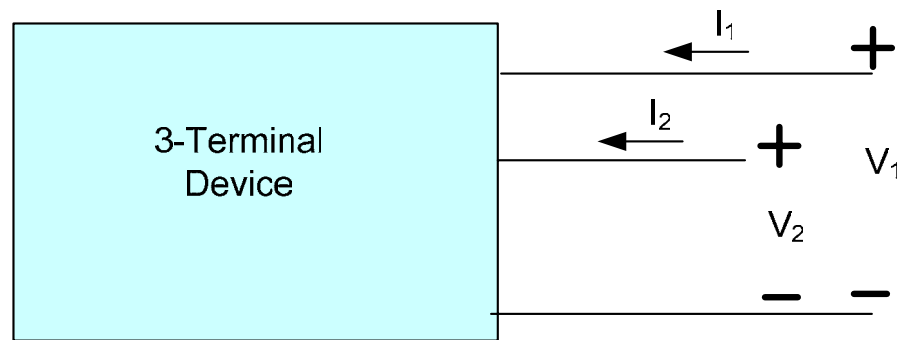
EE 434

Lecture 14

Devices in Semiconductor Processes

Quiz 10

We saw that there were 80 different ways to represent equivalent models for a 4-terminal device with these difference representations being determined by which terminal of the device is selected as a reference and by which port variables are assumed to be independent. What is the corresponding number of different ways to represent equivalent models for a 3-terminal device?



And the number is

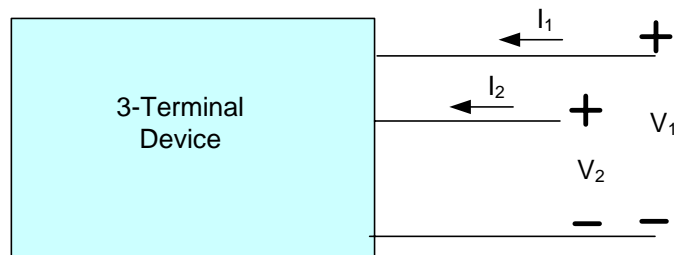
1 8 7 5 3
6 9 4 2

3

Quiz 10

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Solution:



$$\text{Port Variables} = \{I_1, I_2, V_1, V_2\}$$

There are $n_1=3$ ways a reference terminal can be selected

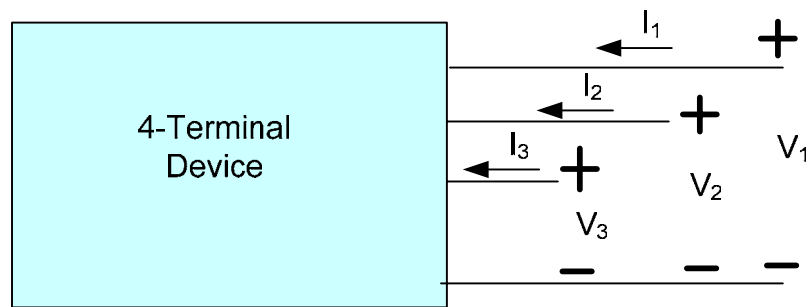
There are a total of 4 port electrical variables and any two of these can be selected as independent variables

$$n = 3 \binom{4}{2} = 3 \frac{4!}{(4-2)!2!} = 18 \quad \left. \begin{array}{l} I_1 = f_1(V_1, V_2) \\ I_2 = f_2(V_1, V_2) \end{array} \right\}$$

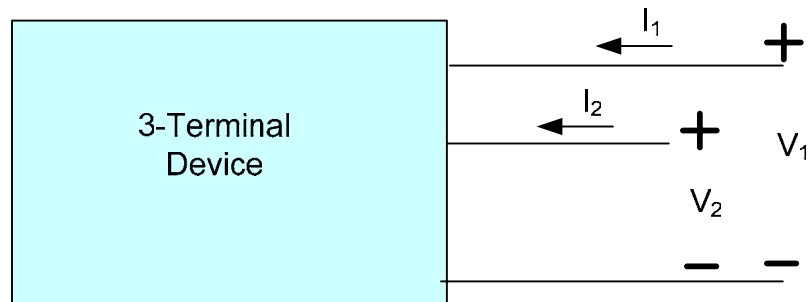
Review from Last Time

Device Modeling

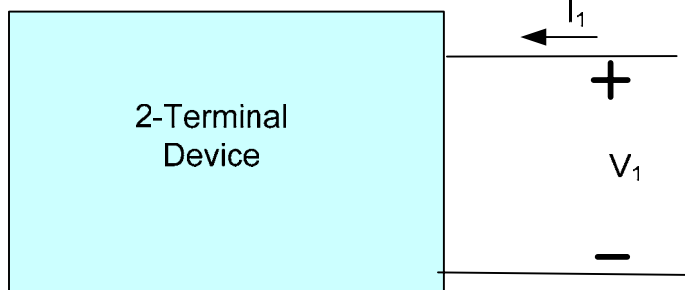
Goal: Obtain a mathematical relationship between the port variables of a device.



$$\left. \begin{aligned} I_1 &= f_1(V_1, V_2, V_3) \\ I_2 &= f_2(V_1, V_2, V_3) \\ I_3 &= f_3(V_1, V_2, V_3) \end{aligned} \right\}$$



$$\left. \begin{aligned} I_1 &= f_1(V_1, V_2) \\ I_2 &= f_2(V_1, V_2) \end{aligned} \right\}$$



$$\left. I_1 = f_1(V_1) \right\}$$

Review from Last Time

Resistors are film devices since vertical dimensions small compared to lateral dimensions

Almost any layer can be (and is) used to form a resistor

Some have more attractive linearity or area requirements

Poly often material of choice for resistors

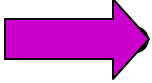
Voltage and Temperature performance characterized by VCR and TCR

$$\mathbf{VCR} = \left(\frac{1}{R} \frac{dR}{dV} \right) \Bigg|_{\text{ref voltage}}^{10^6} \quad \mathbf{ppm/V} \quad R(T_2) \approx R(T_1) \left[1 + (T_2 - T_1) \frac{\mathbf{TCR}}{10^6} \right]$$

$$\mathbf{TCR} = \left(\frac{1}{R} \frac{dR}{dT} \right) \Bigg|_{\text{op. temp}}^{10^6} \quad \mathbf{ppm/^{\circ}C} \quad R(V_2) \approx R(V_1) \left[1 + (V_2 - V_1) \frac{\mathbf{VCR}}{10^6} \right]$$

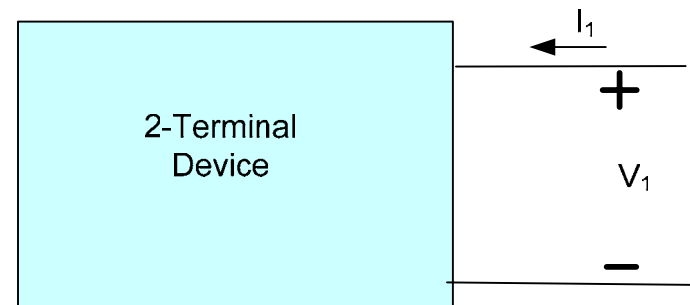
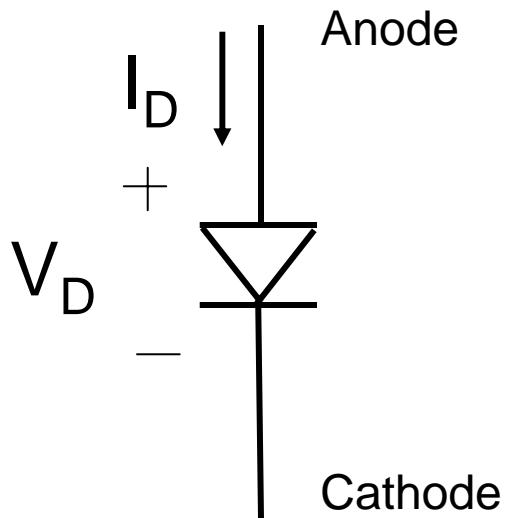
Conductivity of copper more attractive than that of aluminum

Basic Devices and Device Models

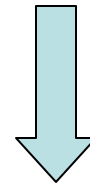
- Resistor
-  • Diode
- Capacitor
- MOSFET
- BJT

Diode Operation and Model

Goal: Obtain a mathematical relationship between the port variables of the diode

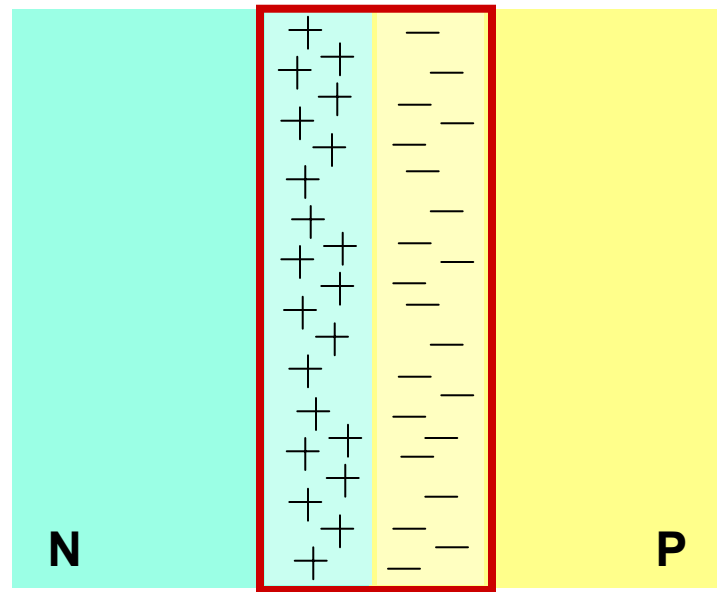


$$I_1 = f_1(V_1) \quad \}$$



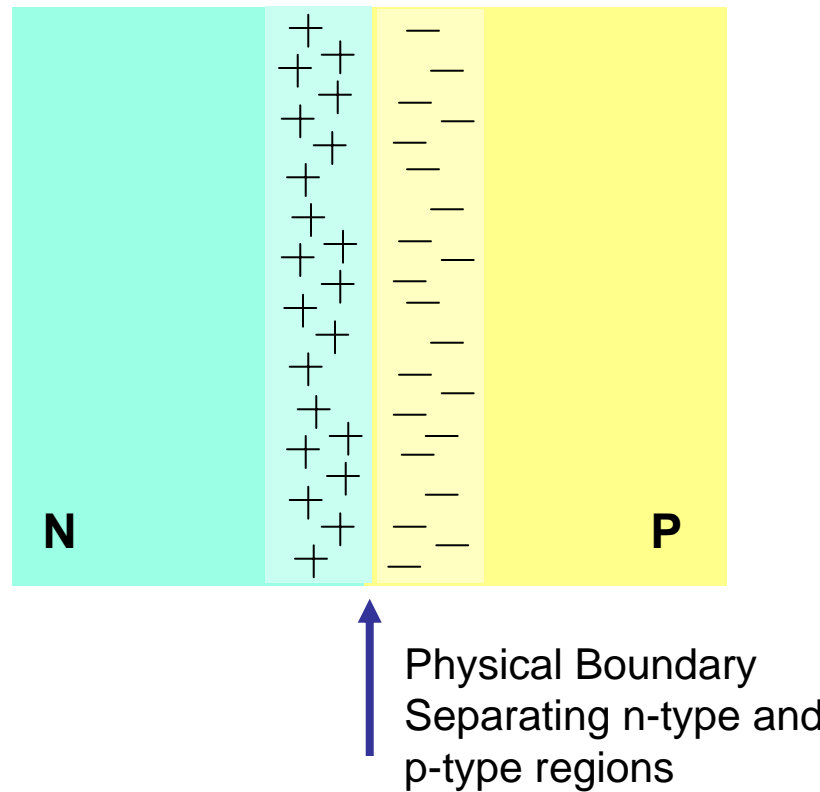
$$I_D = f_1(V_D) \quad \}$$

Diodes (pn junctions)



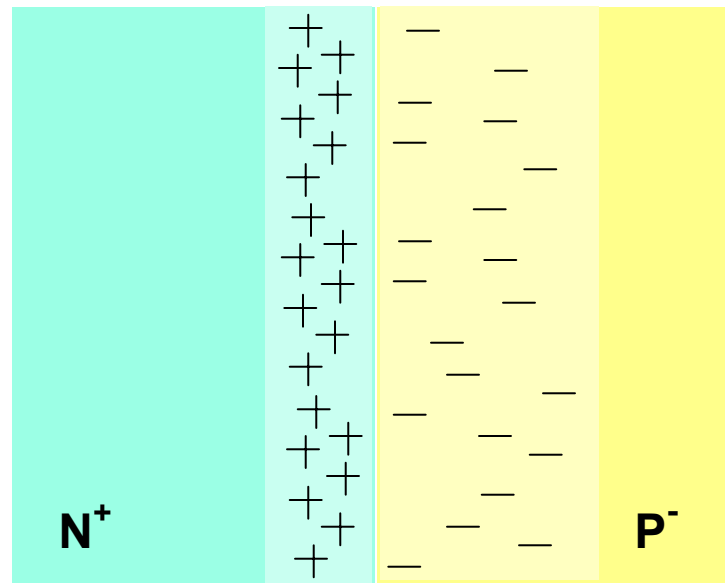
Depletion region created that is ionized but void of carriers

pn Junctions



If doping levels identical, depletion region extends equally into n-type and p-type regions

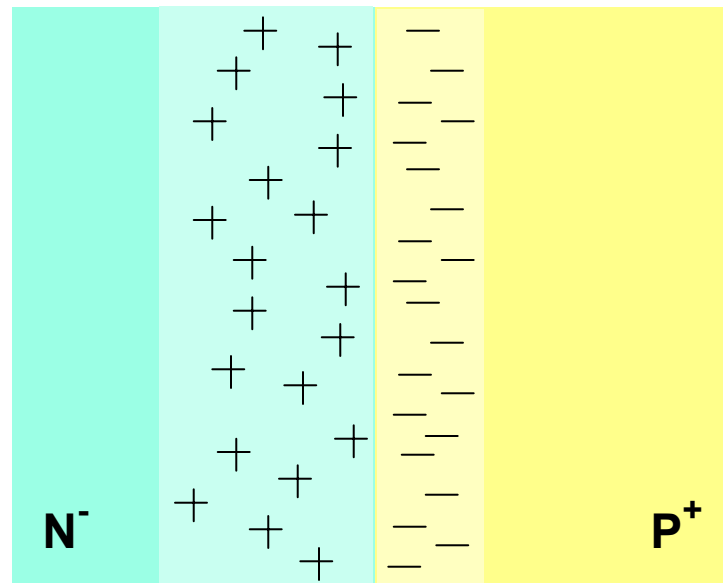
pn Junctions



↑ Physical Boundary
Separating n-type and
p-type regions

Extends farther into p-type region if p-doping lower
than n-doping

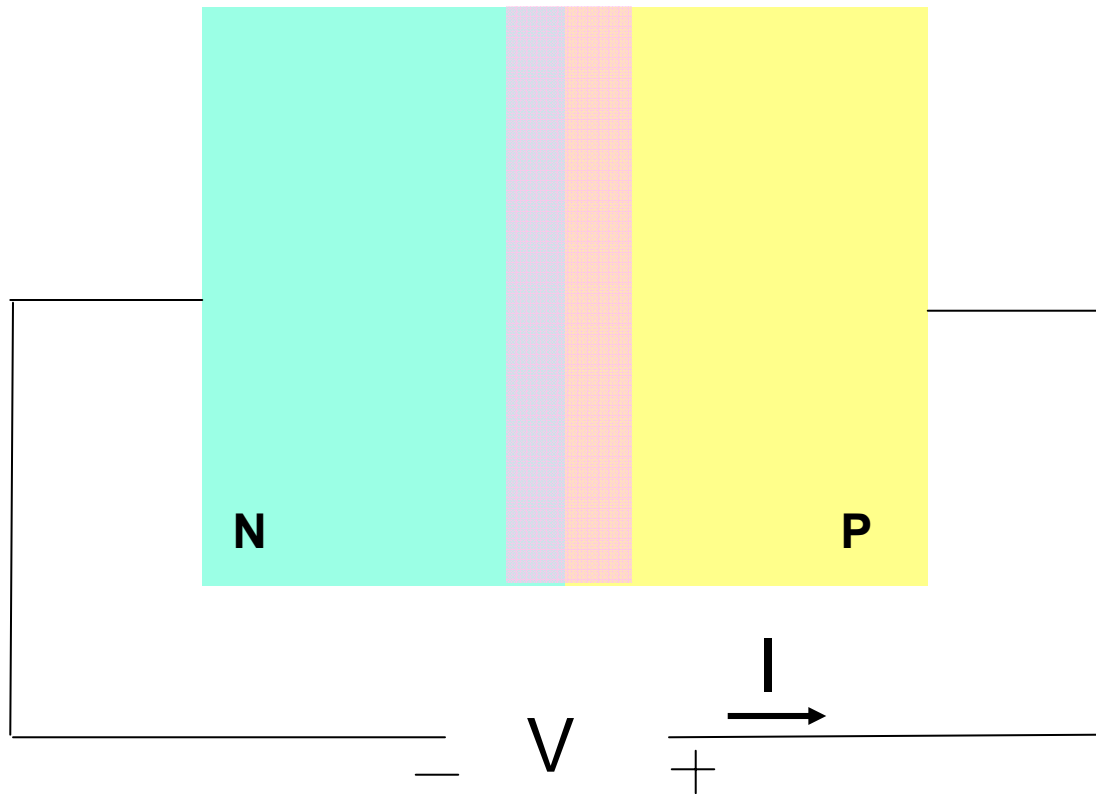
pn Junctions



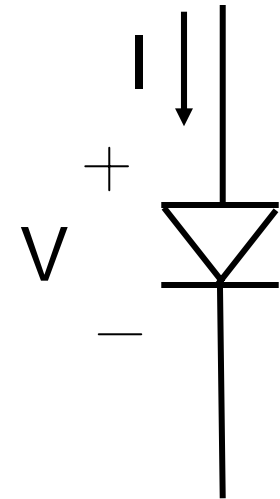
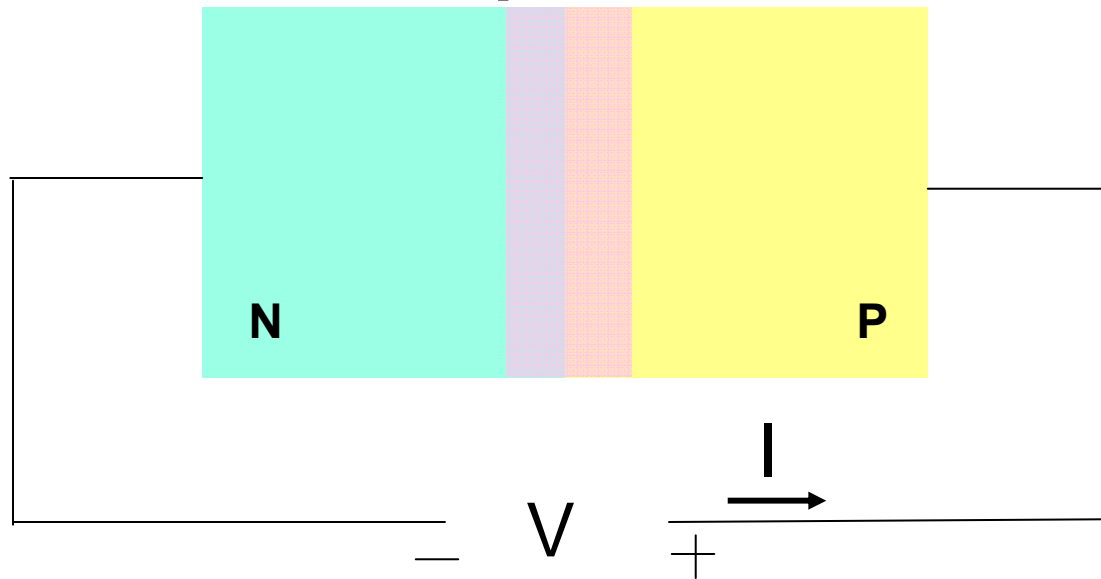
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pn Junctions



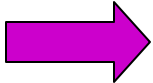
pn Junctions



Diode Equation:
$$I = \begin{cases} J_s A e^{\frac{v}{nV_T}} & V > 0 \\ 0 & V < 0 \end{cases}$$

J_s = Sat Current Density
 A = Junction Cross Section Area
 $V_T = kT/q$
 n is approximately 1

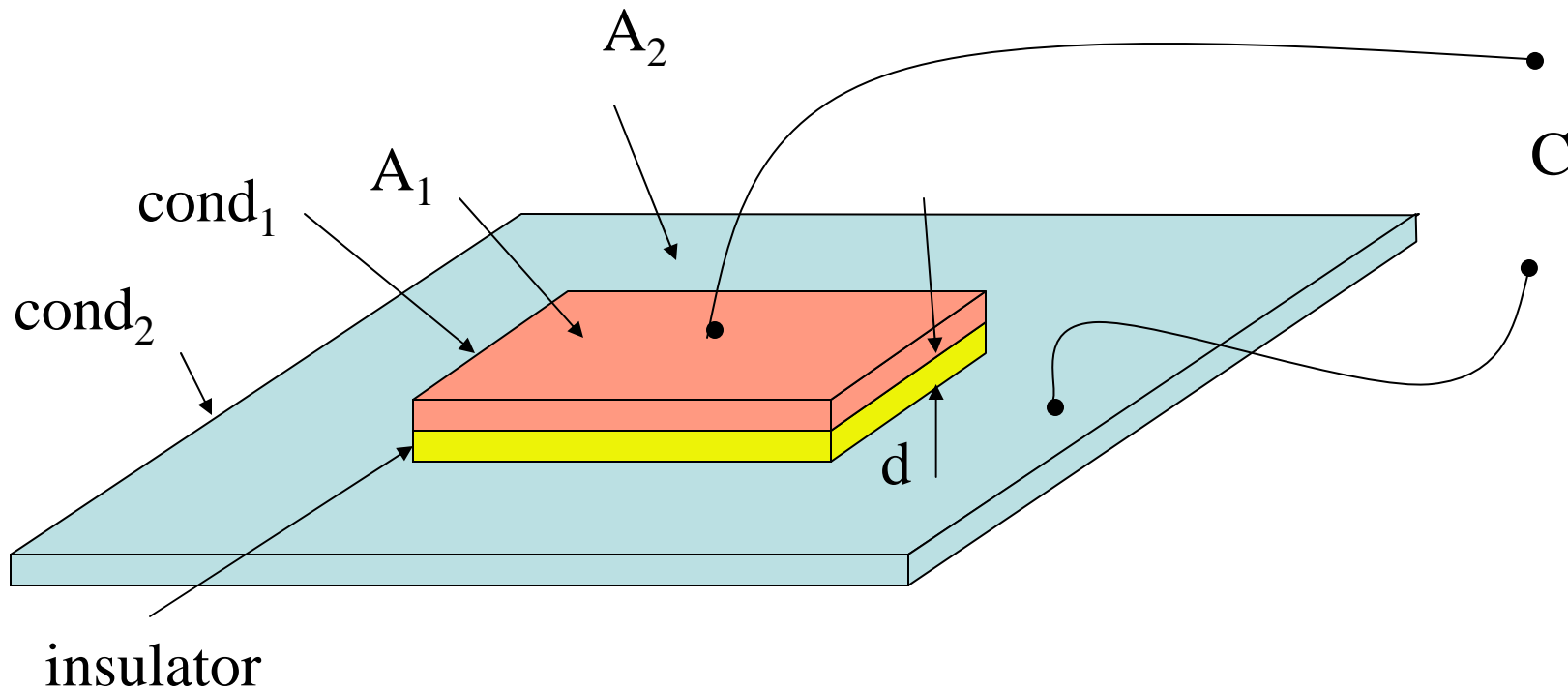
Basic Devices and Device Models

- Resistor
- Diode
-  Capacitor
- MOSFET
- BJT

Capacitors

- Types
 - Parallel Plate
 - Fringe
 - Junction

Parallel Plate Capacitors



A = area of intersection of A_1 & A_2

One (top) plate **intentionally** sized smaller to determine C

$$C = \frac{\epsilon A}{d}$$

ϵ : Dielectric constant

Parallel Plate Capacitors

$$\text{If } C_d = \frac{\text{Cap}}{\text{unit area}}$$

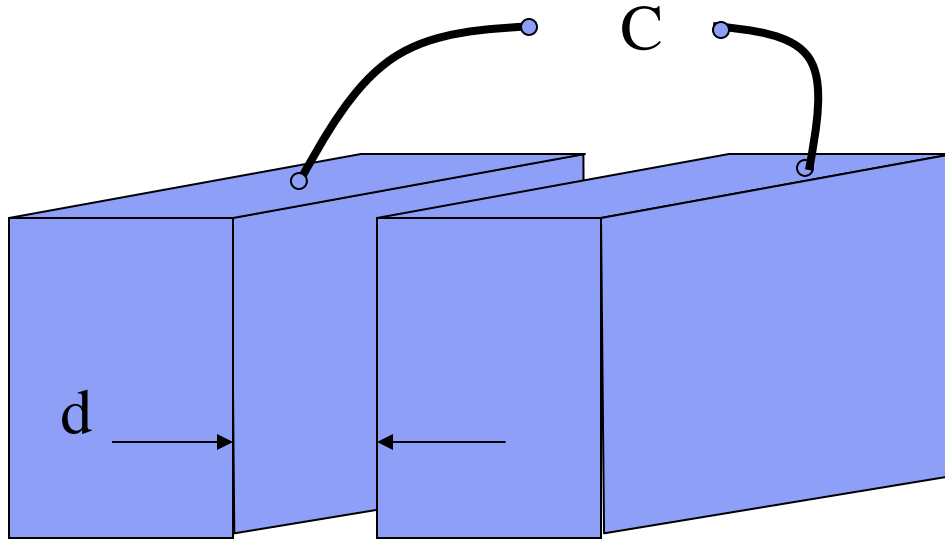
$$C = \frac{\epsilon A}{d}$$

$$C = C_d A$$

where

$$C_d = \frac{\epsilon}{d}$$

Fringe Capacitors

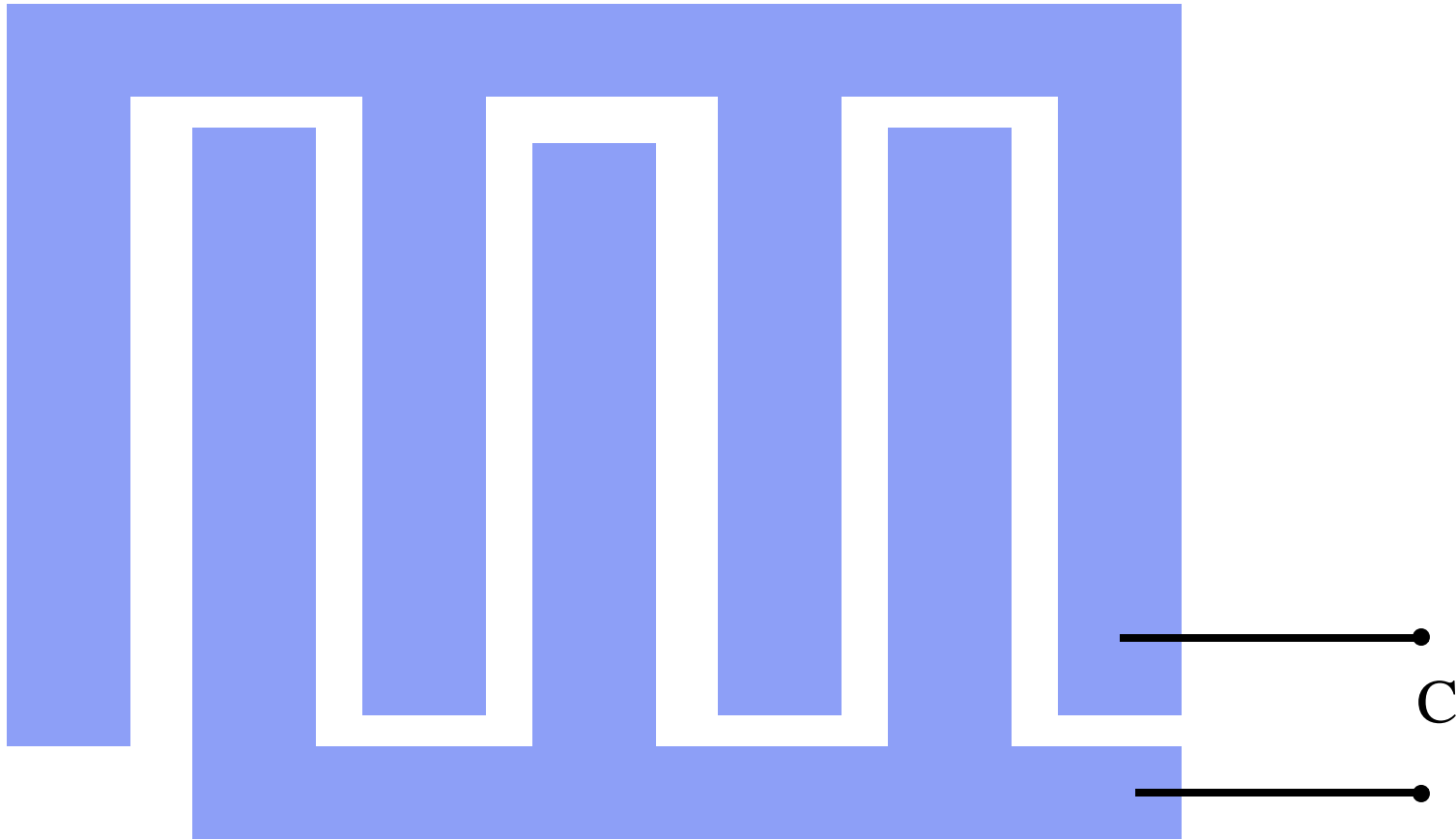


$$C = \frac{\epsilon A}{d}$$

A is the area where the two plates are parallel

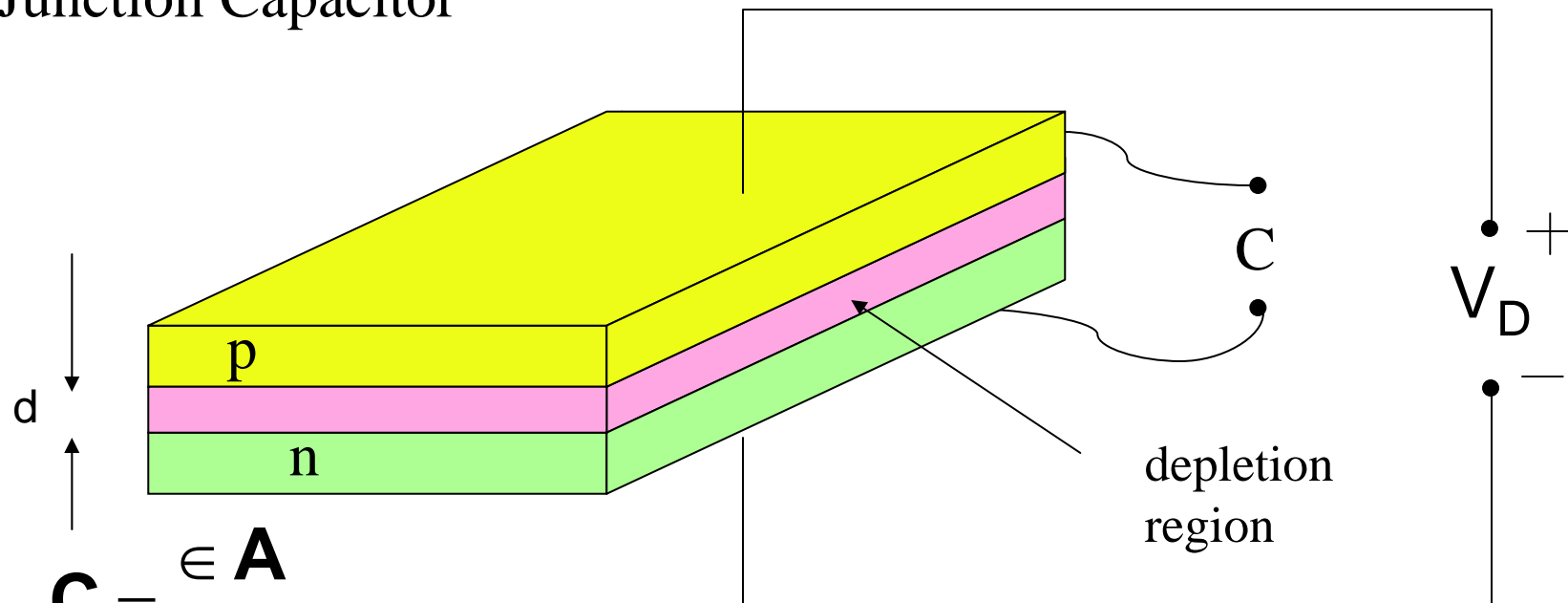
Only a single layer is needed to make fringe capacitors

Fringe Capacitors



Capacitance

Junction Capacitor



$$C = \frac{\epsilon A}{d}$$

$$C = \frac{C_{j0} A}{\left(1 - \frac{V_D}{\phi_B}\right)^n}$$

$$\phi_B \approx 0.6V$$

$$\text{for } V_{FB} < \frac{\phi_B}{2}$$

C_{j0} : junction capacitance at $V_D = 0V$

ϕ_B : barrier or built-in potential

- Note: d is voltage dependent
- capacitance is voltage dependent
 - usually parasitic caps
 - varicaps or varactor diodes exploit voltage dep. of C

End of Lecture 14